



# TEL Clean Track ACT8 SYSTEM

(RNX20200226-06)

2020.02.26



# TEL Clean Track ACT8 System

## Wafer Specification

<b>Wafer Size</b>	<b>200mm</b>	<b>Description</b>	<b>Coater - Developer</b>
<b>Model</b>	<b>ACT8</b>	<b>Vintage</b>	<b>2000</b>

## System Configuration

**UNC : Uni-Cassette Stage**

**HHP : High Temperature Station**

**ADH : Adhesion Process Station**

**CPL : Cool Plate**

**COT : Coat Process Station**

**CPL : Cool Plate**

**TRS : Transition Stage**

**TCP : Transition Chill Plate**

**DEV : Develop Process Station**

**LHP : Low Temperature Station**

**WEE : Wafer Edge Exposure Process Station**

**PCH : Precision Chilling Hot Plate**

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## System Configuration

1-4 UNC	1-0 CRA	2-24 HHP		2-14	3-24 LHP		3-14 LHP	4-0 IRA	4-4 WEE			
		2-23 HHP		2-13 HHP	3-23 PCH		3-13 LHP					
		2-22 LHP		2-12 LHP	3-22 PCH		3-12 LHP					
		2-21 HCP		2-11 CPL	3-21 PCH		3-11 CPL					
		2-20		2-10	3-20		3-10					
1-3 UNC		2-19 CPL	2-29	2-09 CPL	3-19 PCH	3-29	3-09 CPL	4-0 IRA	4-5 EIS			
		2-08 TRS	2-28	2-18 SHU		3-28	3-18					
		2-07 TCP	2-27	2-17 SHU		3-27 LHP	3-17 CPL					
1-2 UNC		2-06	2-26 LHP	2-16	3-6	3-26 LHP	3-16 TRS					
		2-05 ADH	2-25 LHP	2-15 ADH	3-05 CPL	3-25 LHP	3-15 TRS					
1-1 UNC	2-0 PRA			3-0 PRA			4-0 IRA			4-3 Buffer		
	2-3 COT			3-3 DEV		3-4 DEV					4-0 IRA	4-2 Buffer
	2-1 COT		2-2 COT	3-1 DEV								
1-5 PUP	2-1 COT		2-2 COT	3-1 DEV			4-0 IRA			4.1 T. Hold		

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## System Configuration

### External Tool

- 1). Chemical Cabinet #1 (HMDS, Solvent, Developer)
- 2). Chemical Cabinet #2 (PR)
- 3). Thermo Controller Unit #1 (SMC)
- 4). Thermo Controller Unit #2 (SMC)
- 3). AC Power Box

### Machine Detail Information

#### 2-1). Carrier Station

- Type : Normal Uni-Cassette Type
- 4 Cassette Stage, 1 Pick-up Cassette

#### 2-2). Coater Unit

- 4 Dispense Nozzle with Temperature Controlled Line for Etch Unit
- Mini RRC Pump
- Rinse Nozzle : Back / EBR / Solvent Batch for with Unit
- Rinse System : 3 Litter 2 Tank Buffer Tank System

# TEL Clean Track ACT8 System

## Machine Detail Information

- P. R Suck-Back Valve Type : Suck-Back Valve
- Drain : Direct Drain

### 2-3). Tarc Coater Unit

- 3 Dispense Nozzle with Temperature Controlled Lines for Etch Unit
- Mini RRC Pump
- Rinse Nozzle : Back / EBR / Solvent Batch for with Unit
- Rinse System : 3 Litter 2 Tank Buffer Tank System
- P. R Suck-Back Valve Type : Suck-Back Valve
- Drain : Direct Drain

### 2-4). Developer Unit

- H Nozzle for Each Unit
- 2 Stream Nozzle for DI Rinse and 2 Point for Back Side Rinse on Each Unit
- Developer System : 3 Liter 2 Tank Buffer Tank System
- Developer Temperature Control System
- Drain Direct Drain

# **TEL Clean Track ACT8 System**

## **Machine Detail Information**

**2-5). Interface**

**2-6). Adhesion Unit : 2 Unit**

**- 100% Sealing Closed Chamber (Built-in Hot Plate)**

**- HMDS Tank with Float Sensor in System**

**2-7). Low Temp Hot Plate (LHP) : 11ea**

**2-8). High Temp Hot Plate (HHP) : 3ea**

**2-9). Chill Plate (CPL) : 7ea**

**2-10). Precision Chilling Hot Plate Process Station (PCH) 4EA**

**2-11). TCP Module 1EA**

**2-12). TRS Module : 3EA**

**2-14). HCP Module : 1EA**

**2-15). WEE (Wafer Edge Exposure) Module : 1ea**

**Wafer Type : Notch, DUV Type**

**2-16). Chemical Cabinet #1, Solvent & Developer**

**2-17). Chemical Cabinet #2, PR & HMDS**

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## Machine Detail Information

**2-18). TEMP Control Unit (TCU) 1ea**

**Type : TEL OEM**

**2-19). AC Power Box**

## Missing Parts

- . CSB Motor I/O Board**
- . CSB Add on Board**
- . 3-4 Panasonic Motor**
- . 3-1 Out Cup Cylinder**
- . 3-1 Arm 2, Arm 1 Motor**
- . PRB2 Chemical IO Board**
- . T&H Controller (For 4 Cup)**
- . 2-0 PRA X Motor Driver, 4-0 IRA Z Motor Driver**
- . 4-0 IRA UPS, 4-0 IRA Motor IO Board, 4-0 IRA IFB Add on Board**
- . WEE Theta Driver**
- . HDD**

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Machine no.



Main Controller



Coater Module (2-1)



Coater Module (2-2)



Coater Module (2-3)



PRB2 Spin Driver



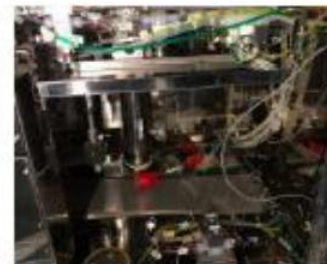
PR Pump Area (Front)



PR Pump Area (Rear)



COT Chemical (L)



COT Chemical (R)



DEV Module (3-1)



DEV Module (3-3)



DEV Module (3-4)



DEV Chemical Area



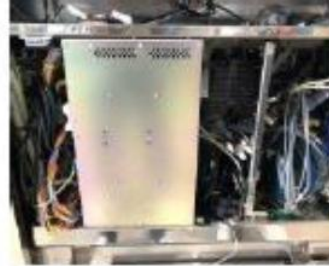
DEV Chemical (R)



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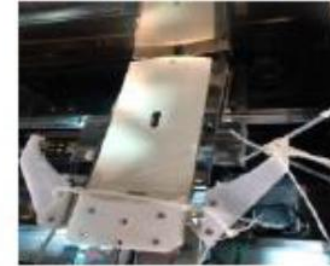
PRB3 Driver Area



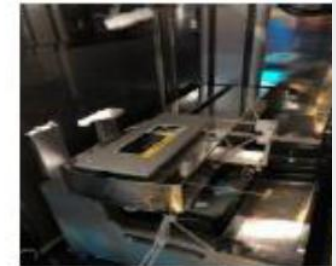
DC Power Box



CSB Board Area



CRA



IRA



PR Cabinet



HMDS Buffer Tank



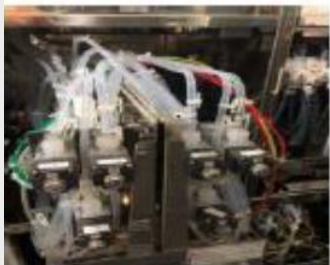
CSB & PRB1



PRB3



Chemical Cabinet



Solvent Filter Area



Thermo Controller #1



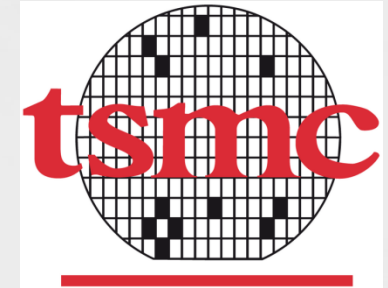
InterFace



AC Power



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